In the Claims

1. (Currently Amended) A method for producing an aromatic compound isomer substituted with alkyl group(s) and/or halogen atom(s)~~, through~~comprising subjecting a starting mixture containing the aromatic compound isomer to adsorptive separation by the use of a zeolite-containing adsorbent and a desorbent, ~~wherein~~and subjecting the desorbent ~~is~~to a method selected from the group consisting of distillation, purging, and absorption to a solid absorbent to achieve a level below 1,000 ppm by weight, supplied to adsorptive separation such that, after having been processed for removing impurities, the desorbent is selected from the group consisting of water, hydrochloric acid, phenols, dimers of aromatic compounds, unsaturated hydrocarbon-containing compounds and oxygen-containing compounds~~ from it by a method selected from distillation, purging, or absorption to a solid absorbent to achieve a level below 1,000 ppm by weight, supplied to the adsorptive separation step~~.

2. (Original) The method for producing an aromatic compound isomer as claimed in claim 1, wherein the aromatic compound has a benzene ring or heterocyclic ring structure.

3. (Original) The method for producing an aromatic compound isomer as claimed in claim 1 or 2, wherein the aromatic compound is ring-substituted with at least one halogen element.

4. (Cancelled)

5. (Previously Presented) The method for producing an aromatic compound isomer as claimed in claim 1, wherein the impurities in the desorbent are removed by replacing a part of the used desorbent with an impurity-free fresh desorbent.

6. (Currently Amended) The method for producing an aromatic compound isomer as claimed in claim 1, wherein all or part of the desorbent to be supplied to the adsorptive separation ~~step~~ is first continuously or intermittently supplied to a step of removing impurities from it, and then

supplied to the adsorptive separation ~~step~~.

7. (Currently Amended) A method for producing an aromatic compound isomer substituted with alkyl group(s) and/or halogen atom(s)~~, through~~comprising subjecting a starting mixture containing the aromatic compound isomer to adsorptive separation by the use of a zeolite-containing adsorbent and a desorbent, ~~wherein~~and subjecting the desorbent ~~is~~ to a method selected from the group consisting of distillation, purging, and absorption to a solid absorbent to achieve a level below 1,000 ppm by weight, supplied to adsorptive separation such that, after having been processed for removing oxygen-containing or high boiling point compound impurities, the desorbent is selected from the group consisting of water, hydrochloric acid, phenols, dimers of aromatic compounds, unsaturated hydrocarbon-containing compounds and oxygen-containing compounds~~from it by a method selected from distillation, purging, or absorption to a solid absorbent to achieve an impurity level of ≤1,000 ppm by weight, supplied to the adsorptive separation step~~.

8. (Currently Amended) A method for producing an aromatic compound isomer substituted with alkyl group(s) and/or halogen atom(s)~~, through~~comprising subjecting a starting mixture containing the aromatic compound isomer to adsorptive separation by the use of a zeolite-containing adsorbent and a desorbent, ~~wherein~~and subjecting the desorbent ~~is~~to a method selected from the group consisting of distillation, purging, and absorption to a solid absorbent to achieve a level below 1,000 ppm by weight, supplied to adsorptive separation such that, after having been processed for removing impurities having an aldehyde group or a carboxyl group, the desorbent is selected from the group consisting of water, hydrochloric acid, phenols, dimers of aromatic compounds, unsaturated hydrocarbon-containing compounds and oxygen-containing compounds ~~from it by a method selected from distillation, purging, or absorption to a solid absorbent to achieve an impurity level of ≤1,000 ppm by weight supplied to the adsorptive separation step~~.

9. (Currently Amended) A method for producing an aromatic compound isomer substituted with alkyl group(s) and/or halogen atom(s)~~, through~~comprising subjecting a starting mixture containing the aromatic compound isomer to adsorptive separation by the use of a zeolite-containing adsorbent and a desorbent, ~~wherein~~and subjecting the desorbent ~~is~~to a method selected from the group consisting of distillation, purging, and absorption to a solid absorbent to achieve a level below 1,000 ppm by weight, supplied to adsorptive separation such that, after having been processed for removing impurities produced during adsorptive separation, the desorbent is selected from the group consisting of water, hydrochloric acid, phenols, dimers of aromatic compounds, unsaturated hydrocarbon-containing compounds and oxygen-containing compounds ~~from it by a method selected from distillation, purging, or absorption to a solid absorbent to achieve an impurity level of ≤1,000 ppm by weight, supplied to the adsorptive separation step~~.

10. (Currently Amended) A method for producing an aromatic compound isomer substituted with alkyl group(s) and/or halogen atom(s)~~, through~~comprising subjecting a starting mixture containing the aromatic compound isomer to adsorptive separation by the use of a zeolite-containing adsorbent and a desorbent, ~~wherein~~and subjecting the desorbent ~~is~~ to a method selected from the group consisting of distillation, purging, and absorption to a solid absorbent to achieve a level below 1,000 ppm by weight, supplied to adsorptive separation such that, after having been processed for removing oxygen-containing or high boiling point compounds impurities produced during adsorptive separation having an adehyde group or a carboxyl group, the desorbent is selected from the group consisting of water, hydrochloric acid, phenols, dimers of aromatic compounds, unsaturated hydrocarbon-containing compounds and oxygen-containing compounds ~~from it by a method selected from distillation, purging, or absorption to a solid absorbent to achieve an impurity level of ≤1,000 ppm by weight, supplied to the adsorptive separation step~~.